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PRESS RELEASE

From NANONEX

NANONEX DELIVERS BREAKTHROUGH TECHNOLOGY TO THE UNIVERSITY OF MICHIGAN

Princeton NJ, Sept. 26, 2003: Nanonex Corp. the world-leading developer and manufacturer of nanoimprint lithography solutions, recently announced the installation of its ***Nanonex 1000***® *upgradeable thermal imprintor* at the University of Michigan, Ann Arbor Campus. The Department of Electrical Engineering and Computer Science, one of the largest and most distinguished academic EE & CS programs in the country, houses the *Nanonex 1000*® . The University anticipates the new tool will be used in research and production applications including spectroscopy of quantum dots, quantum computing, spectroscopy of solids, cavity quantum electrodynamics, holography including imaging through tissue such as for optical mammography and biophysical studies of biomolecular structure.

> *"NIL can have sub-5 nm resolution and 1% CD control, and simultaneously achieve high-throughput, sub-10 nm structures and low cost -- a feat currently impossible using other existing lithographic methods"*
>
> *Professor Stephen Y. Chou, Chairman, Nanonex*

Nanoimprint lithography (NIL) is a breakthrough method of nanopatterning and a revolutionary solution to nanomanufacturing. NIL patterns nanostructures by physically deformation of a deformable material using a mold. NIL can have sub-5 nm resolution and 1% CD control, and simultaneously achieve high-throughput, sub-10 nm structures and low cost -- a feat currently impossible using other existing lithographic methods. The *Nanonex 1000*® is capable of performing all aspects of thermal nanoimprinting, including thermal and photocurable NIL and direct nanoimprinting. The company and its proprietary technology has been developed on the pioneering research of renowned expert Prof. Stephen Y. Chou, Founder and Chairman of the firm.

About Nanonex Corporation. Headquartered in Princeton, NJ with offices in California, Nanonex provides a complete line of nanonimprint lithography (NIL) technology solutions including tools, resists, masks, and processes. Nanonex NIL solution offers sub-10 nm features, 3D patterns, large area uniformity, accurate overlay alignment, high-throughput, and low cost. Nanonex NIL solution includes all forms of nanoimprinting, such as thermal plastic, uv-curable, thermal curable, and direct imprinting (embossing). Nanonex NIL solution can meet the needs of a broad spectrum of markets, such as optical devices, displays, data storage, biotech, IC, chemical synthesis, and advanced materials. Visit www.nanonex.com for additional corporate background and contact information.

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